

**Stabilizing an ultrathin MoS<sub>2</sub> layer during electrocatalytic hydrogen evolution  
with a crystalline SnO<sub>2</sub> underlayer**

**Supporting Information**

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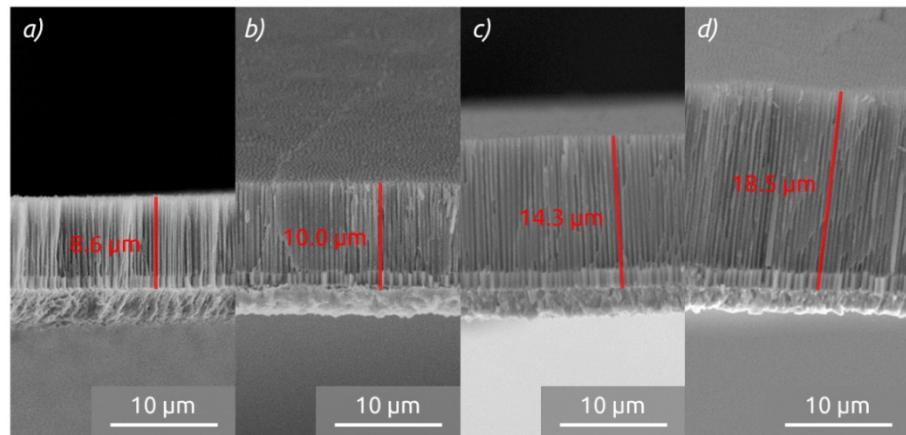
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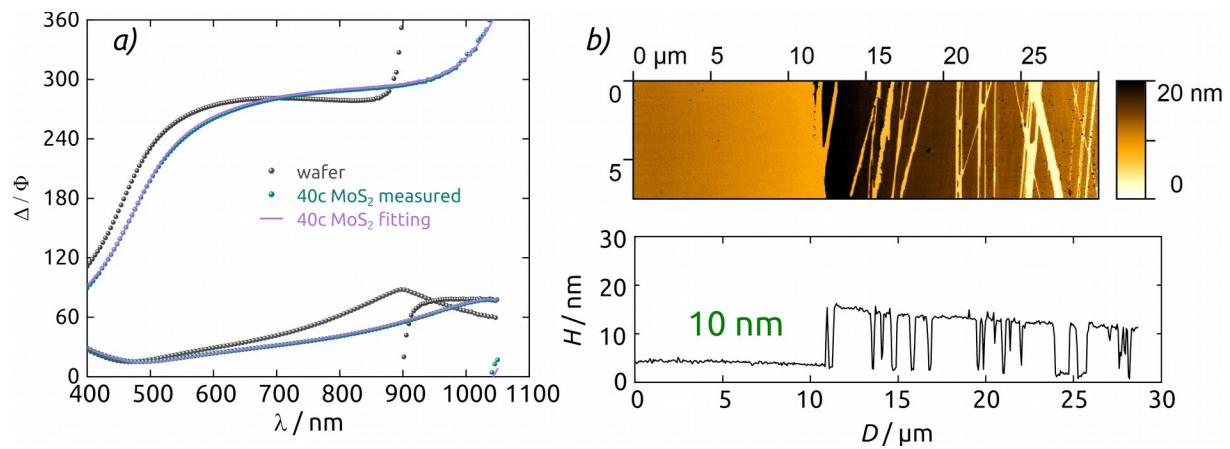
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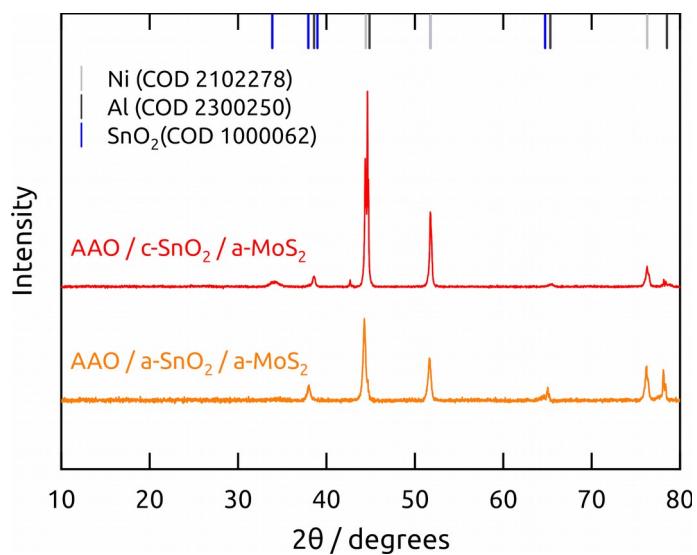
**Keywords:** atomic layer deposition, anodic alumina, tin oxide, molybdenum sulfide, hydrogen evolution reaction, water splitting



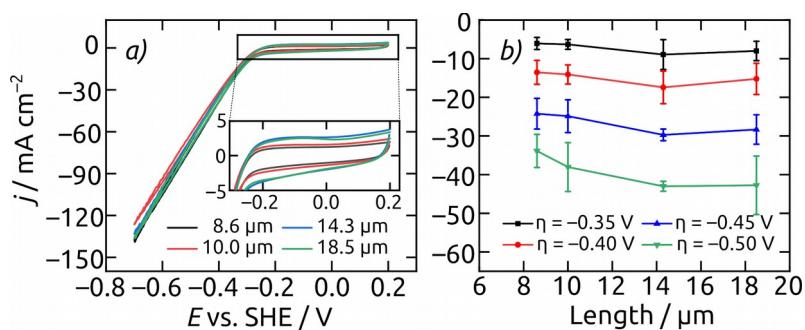
**Figure S1.** Cross-section scanning electron micrographs of AAO membranes anodized for *a)* 3 h, *b)* 4 h, *c)* 6 h or *d)* 8 h in 1 wt-% phosphoric acid at 195 V.



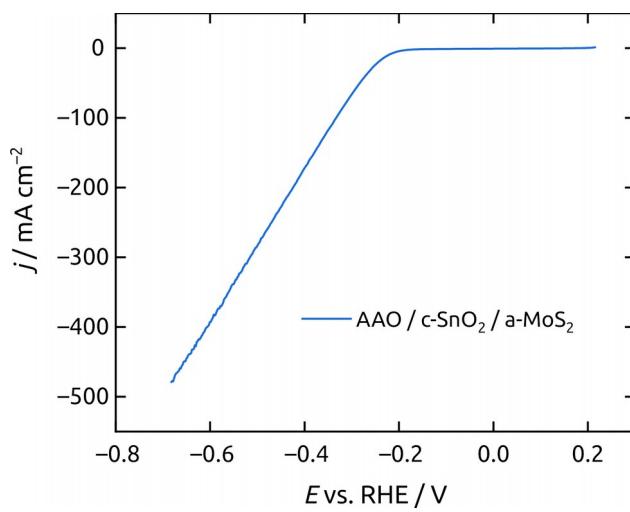
**Figure S2.** Thickness characterization of 40 c atomic layer deposited  $\text{MoS}_2$  films. *a)* Spectroscopic ellipsometry: measured and fitted curves in dots and solid line, respectively; the fit yields an  $\text{MoS}_2$  thickness of 9 nm. *b)* Step edge measurement by AFM, yielding a thickness of 10 nm.



**Figure S3.** X-ray diffraction pattern of AAO / SnO<sub>2</sub> / MoS<sub>2</sub> composite electrodes. Comparison of samples with an as-deposited SnO<sub>2</sub> film (orange) and an annealed SnO<sub>2</sub><sup>T</sup> film (red). All electrodes feature 10 nm SnO<sub>2</sub>, 40 c of MoS<sub>2</sub> and pore lengths of 18.5 μm. Diffraction peaks corresponding to Al (from frame; COD 2300250) and Ni (from backside-contact; COD 2102278) were observed for both samples. The annealed sample features diffraction peaks corresponding to crystalline cassiterite (COD 1000062). No crystalline MoS<sub>2</sub> was observed.



**Figure S4.** Electrocatalytic performance of AAO / c-SnO<sub>2</sub> / MoS<sub>2</sub> composite electrodes for different pore lengths: 8.6 μm (black), 10.0 μm (red), 14.3 μm (blue) and 18.5 μm (green). a) Cyclic voltammograms, measured from +0.2 V to −0.7 V (vs. SHE), scan rate 50 mV/s, step size 2 mV. b) Average steady-state current densities vs. pore length for various applied potentials (vs. SHE). The electrodes feature a 20 nm thick c-SnO<sub>2</sub> layer and 40 c of MoS<sub>2</sub>. Electrode area 0.0314 cm<sup>2</sup>, performed in 0.1 M H<sub>2</sub>SO<sub>4</sub> electrolyte.



**Figure S5.** Linear sweep voltammogram for an AAO / c-SnO<sub>2</sub> / a-MoS<sub>2</sub> composite electrode featuring pore lengths of 8.6 μm, a 20 nm c-SnO<sub>2</sub> film and 40 c of MoS<sub>2</sub>, recorded from +0.22 V to -0.68 V (vs. RHE). Scan rate 50 mV/s, step size 2 mV, electrode area 0.0314 cm<sup>2</sup>. Performed in 0.5 M H<sub>2</sub>SO<sub>4</sub> electrolyte.

**Table S1.** EIS fit parameters. All measurements performed in 0.1 M H<sub>2</sub>SO<sub>4</sub> electrolyte.

MoS <sub>2</sub> thickness / ALD cycles	R <sub>u</sub> / Ω	R <sub>ct</sub> / Ω	α <sub>ls</sub>	Y <sub>ls</sub> / 10 <sup>-6</sup> Ss <sup>α</sup>
10	82.5	12900	0.949	103
25	104	1210	0.921	303
40	79.8	107	0.896	824
75	98.7	109	0.789	1130

**Table S2.** Comparison of the HER activities of different amorphous MoS<sub>2</sub> based electrocatalysts.

Electrodes	Loading (mg/cm <sup>2</sup> )	Current density (mA/cm <sup>2</sup> )	Overpot. (mV)	Electrolyte (H <sub>2</sub> SO <sub>4</sub> )	preparation (catalysts)	Ref. in main text
MoS <sub>x</sub> /PDOPA@MWCNTs <sup>a</sup>	0.283	10	214	0.5 M	Wet chemical	[11]
MoS <sub>3</sub>	0.2	10	160	1 M	Electrodeposition	[41]
MoS <sub>6</sub> AD <sup>b</sup>	0.1	10	161 <sup>c</sup>	0.5 M	Electrodeposition	[42]
MoS <sub>x</sub> QD <sup>d</sup>	---	5	800	0.5 M	Wet chemical	[40]
MoS <sub>2</sub> /graphene foam	---	10	264	0.5 M	Atomic layer deposition	[43]
MoS <sub>x</sub> /N-doped CNT <sup>e</sup>	---	10	110	0.5 M	Wet chemical	[46]
MoS <sub>2</sub> /TNTAs <sup>f</sup>	1.2	10	189	0.5 M	Atomic layer deposition	[9]
a-MoS <sub>x</sub> /PbTe QD <sup>d</sup> /TNA <sup>f</sup>	4.5	10	138 <sup>c</sup>	0.5 M	Electrochemical anodization	[44]
MoS <sub>x</sub>	0.05	10	210	0.5 M	Wet chemical	[45]
MoS <sub>2</sub> /SnO <sub>2</sub> /AAO <sup>g</sup>	0.16 <sup>h</sup>	10	220	0.5 M	Atomic layer deposition	<b>This work</b>

<sup>a</sup>polydihydroxyphenylalanine (PDOPA), multiwalled carbon nanotubes (MWCNTs),

<sup>b</sup>anodic deposition, <sup>c</sup>resistance-corrected, <sup>d</sup>quantum dots, <sup>e</sup>carbon nanotubes,

<sup>f</sup>titanium oxide nanotubes arrays, <sup>g</sup>anodic aluminum oxide, <sup>h</sup>The catalyst loading was calculated assuming a perfect hexagonal structure with an edge length of 310 nm, a pore diameter after SnO<sub>2</sub> ALD of 340 nm and pore lengths of 7.5 μm (averaged values, determined by SEM).